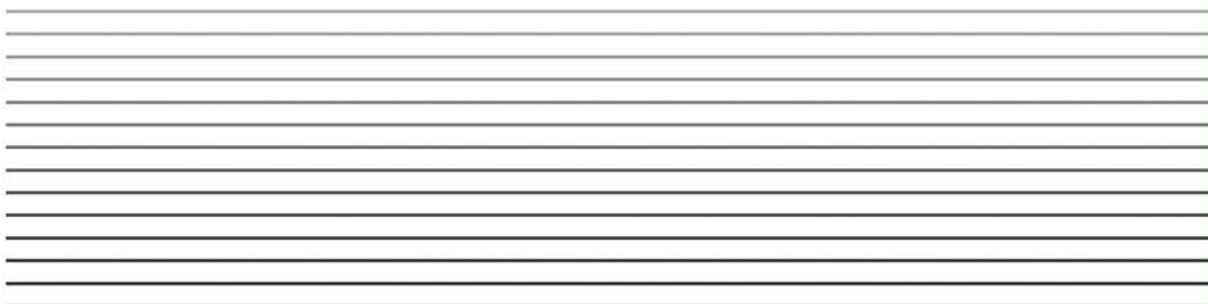


VAKSiS

R&D AND ENGINEERING

MIDAS®



PRODUCT INFORMATION

Vaksis MIDAS COATING SYSTEMS platforms are composed of prismatic vacuum chambers and involve the techniques and combinations below:

CONFIGURATION MATRIX

Techniques	Magnetron Sputtering (MS)	Thermal Evaporation (Th E)	Electron Beam (e-Beam)	Organic and Metal Evaporation (OLED/OPV)	Multi Tech.
MIDAS	✓	✓	✓	✓	MS, Th E, e-Beam, OLED/OPV

TECHNICAL SPECIFICATIONS

Ultimate Vacuum Pressure	$\leq 5 \times 10^{-8}$ Torr
Substrate Size	4"- 8" diameter
Substrate Heating	max. 800°C
Substrate Rotation	3-30 rpm
Cooling.....	Where necessary
Deposition Mode	Upward
Load Lock Chamber	Optional
Control	Fully Automatic

POWER SOURCES

- DC and/or RF Power Supply for Sputtering Magnetron Source
- Effusion Cell A.C. Power Supply for Metal and/or Organic Evaporation Sources
- High-Current Low-Voltage A.C. Power Supply for Resistive Thermal Evaporation Source
- Power Supply for Electron Beam Evaporation Source

SOFTWARE

System operation by user-friendly software. It is not only the automation and control software but also coating management software which allows the user design his/her specific coating experiments, examine the process parameters used in the past, and use the recipes/coatings developed in the past without hustle.

Human and machine safeties are prime importance in the operations performed by the software. A graphical user interface will allow the user to see the status of the system during operation.